

# Questions for “*in situ* Metrology for Projection Optics Contamination” Breakout Session

1. What are we trying to measure, to what sensitivity do we need to measure it, and how fast does it happen?
2. How do we insure that work on in situ metrology options is of use to EUV exposure tool suppliers?
3. What are the various metrology options? What kind of information can be obtained from these options? How disruptive/ invasive would these options be in the PO Box of an EUVL tool?
4. What is the upper limit, in terms of cost, that could be tolerated for any in situ optics metrology?